

Supporting Information for

**Asymmetric Contact Induced Self-Powered 2D In₂S₃ Photodetector towards
High-Sensitivity and Fast-Response**

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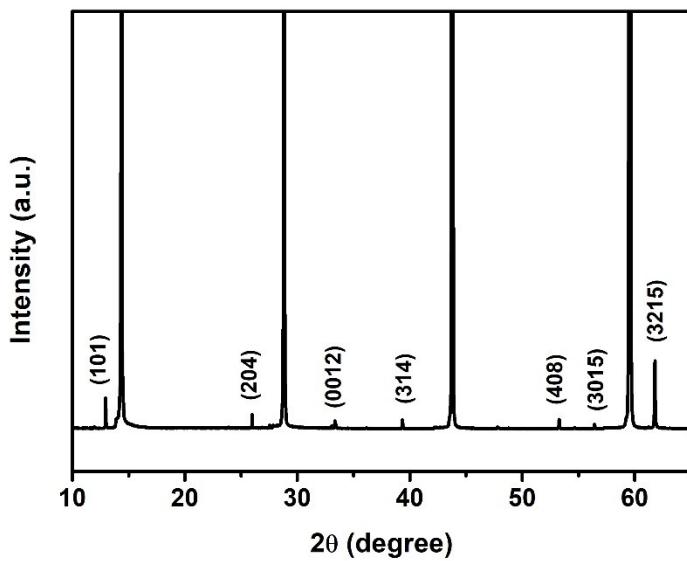


Figure S1. Enlarged XRD pattern of the prepared sample. The weak peaks can be indexed to tetragonal In_2S_3 (JCPDS 73-1366)^{1, 2}. Actually, the tetragonal (JCPDS 73-1366) and cubic (JCPDS 51-1159) phases are only different in the arrangement of vacancies on tetrahedral cation sites, so that they share very similar crystal structure. During the preparation of In_2S_3 samples, environmental disturbances (especially the heating and cooling processes) will affect the defect distribution, resulting in samples with slightly different structures. However, as shown in the XRD pattern, the peak intensity of cubic In_2S_3 is much larger than that of tetragonal In_2S_3 , indicating that the content of tetragonal In_2S_3 is very small and can be ignored.

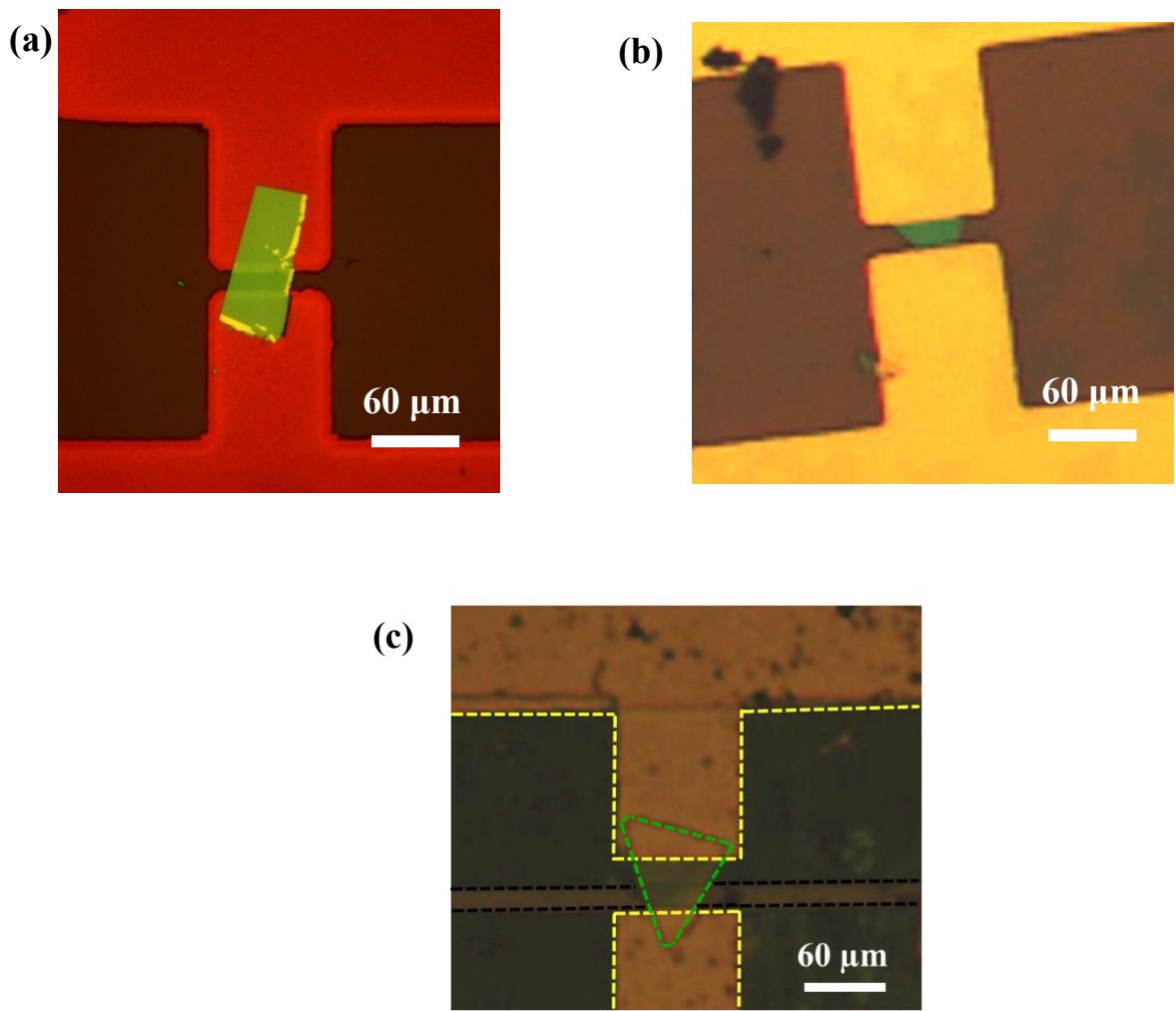


Figure S2. Optical images of the In_2S_3 -based photodetectors with (a) symmetric contact lengths; (b) asymmetric contact lengths. (c) Optical image of the AC- $\text{In}_2\text{S}_3/\text{Si}$ device.

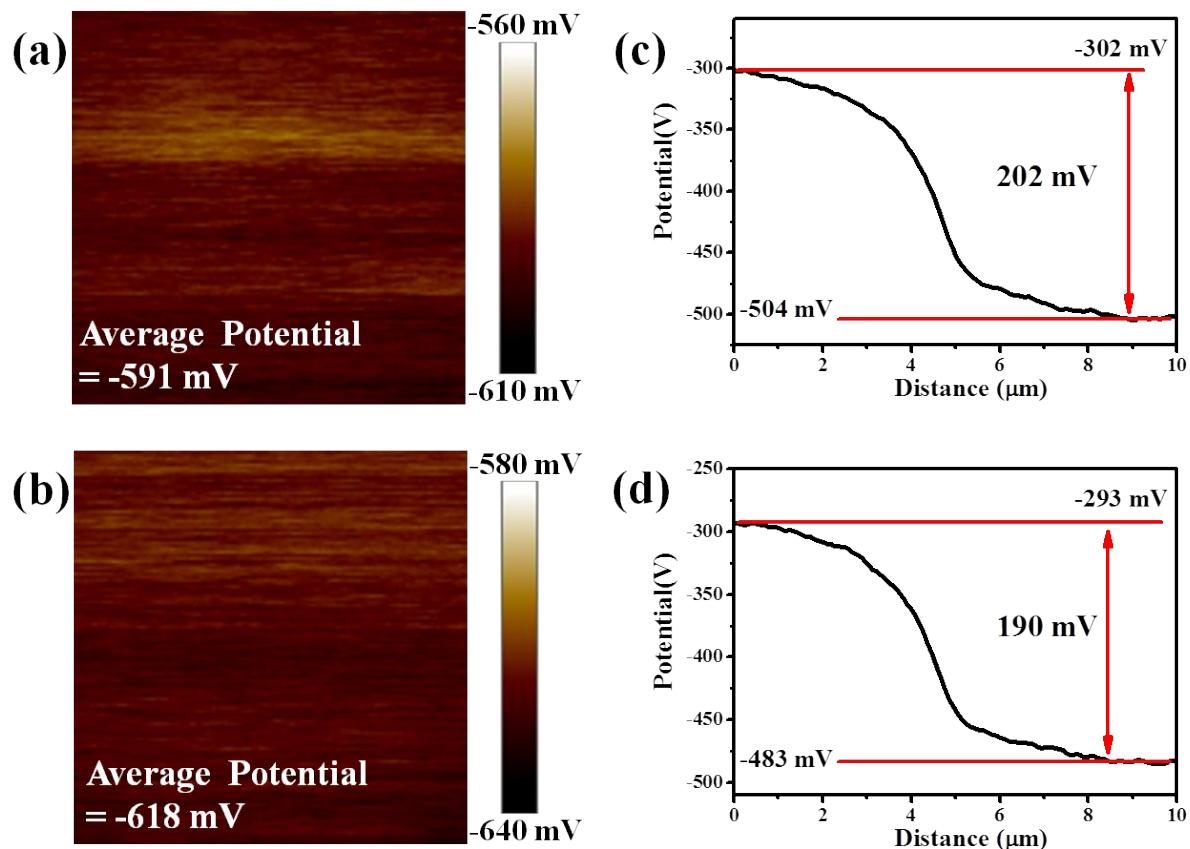


Figure S3. (a) SPD map of Au in dark. (b) SPD map of Au under white light illumination. (c) The calibrated SPD along the heterointerface of In_2S_3 and Si in dark. (d) The calibrated SPD along the heterointerface of In_2S_3 and Si under white light illumination.

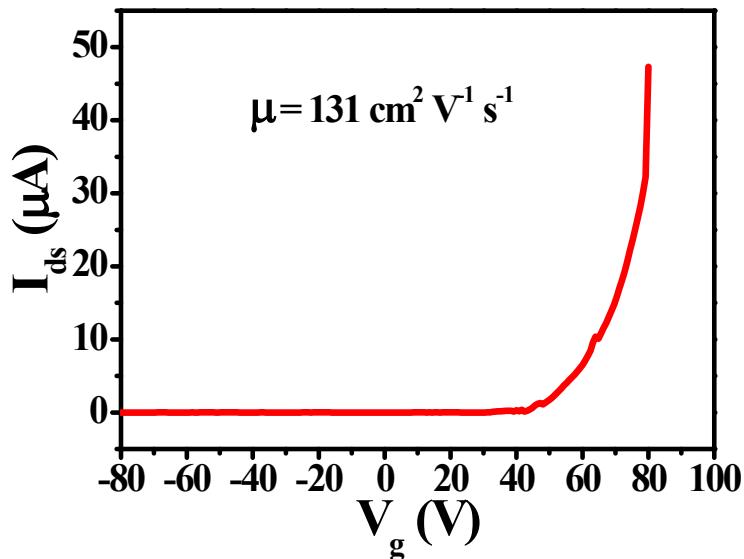


Figure S4. The transfer curve of planar In_2S_3 device. This device was fabricated as follows: The grown In_2S_3 nanoflake was firstly transferred onto the commercially purchased SiO_2 (300nm)/Si substrate. Then, planar Ti/Au (10/100 nm) electrodes were deposited via a stand photolithography process, followed by electron beam evaporation and lift-off process.

The electron mobility can be acquired by the following equation^{3, 4}

$$\mu = \frac{\partial I_{ds}}{\partial V_g} \left(\frac{Ld}{W\epsilon_0\epsilon_r V_{ds}} \right)$$

$$\frac{\partial I_{ds}}{\partial V_g}$$

where L and W are the length and width of the channel, $\frac{\partial I_{ds}}{\partial V_g}$ is slope of the transfer curve, μ is mobility, ϵ_r is the relative static permittivity, ϵ_0 is the electric constant, and d is the thickness of the SiO_2 layer. Herein, $V_{ds} = 2$ V, $L = 3$ μm , $W = 15$ μm , $d = 300$ nm, $\epsilon_0 = 8.85 \times 10^{-12}$ F/m and $\epsilon_r = 3.9$.

$$\frac{\partial I_{ds}}{\partial V_g}$$

Based on the data shown in Figure S2, $\frac{\partial I_{ds}}{\partial V_g} = 1.51 \times 10^{-5}$ A/V. Then, the electron mobility is calculated to be $131 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$.

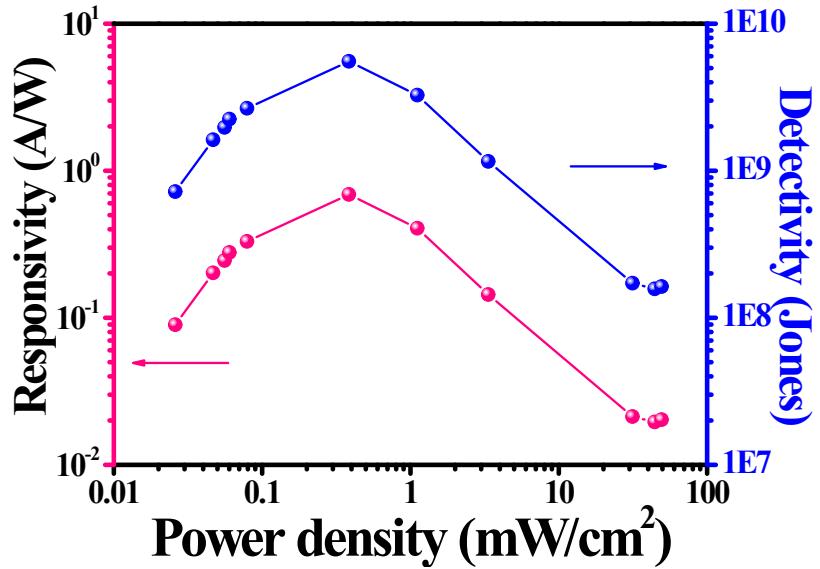


Figure S5. Photoresponsivity and detectivity as a function of incident light intensity of an AC-In₂S₃ device.

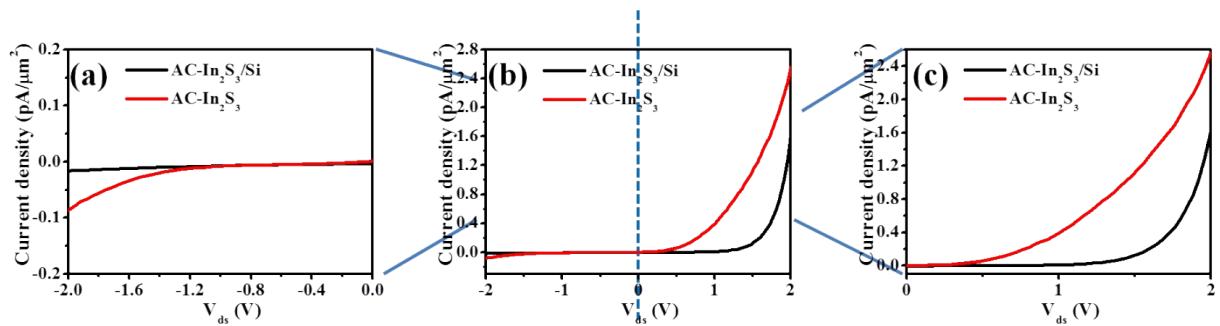


Figure S6. (a) The corresponding I-V curves of AC-In₂S₃ device and AC-In₂S₃/Si device in dark under negative bias. (b) The I-V curves of AC-In₂S₃ device and AC-In₂S₃/Si device in dark. (c) The corresponding I-V curves of AC-In₂S₃ device and AC-In₂S₃/Si device in dark under positive bias.

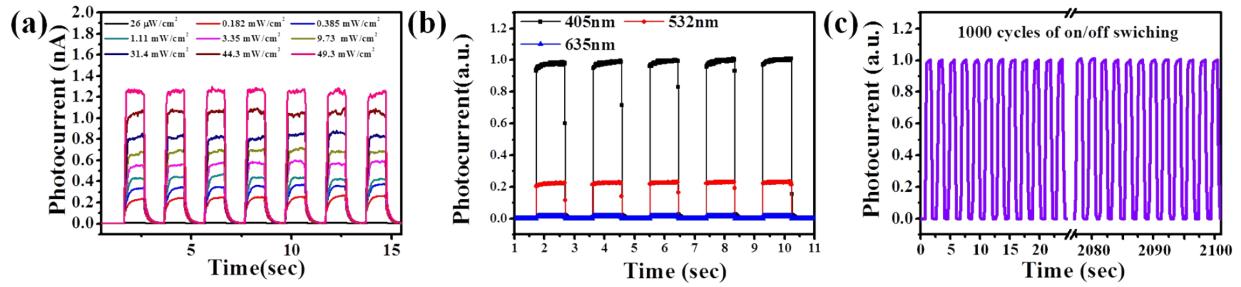


Figure S7. (a) Photoswitching characteristics of the AC-In₂S₃/Si device under various light intensity at $V_{ds} = 0$ V. (b) Stability and repeatability of the photocurrent under incident light with different wavelengths. (c) Photoresponse of the AC-In₂S₃/Si photodetector in 1000 photoswitching cycles.

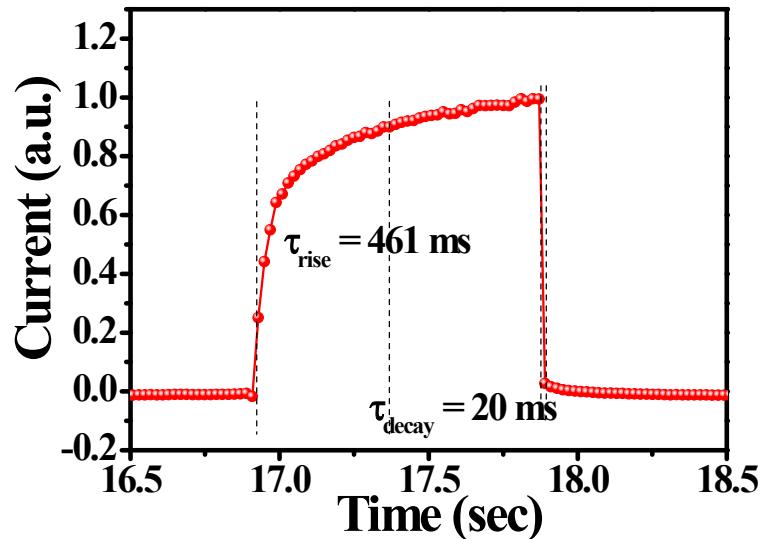


Figure S8. The magnified and normalized plot of one photoswitching cycle of a rectangular-shape In₂S₃ device. The bias voltage is 2 V.

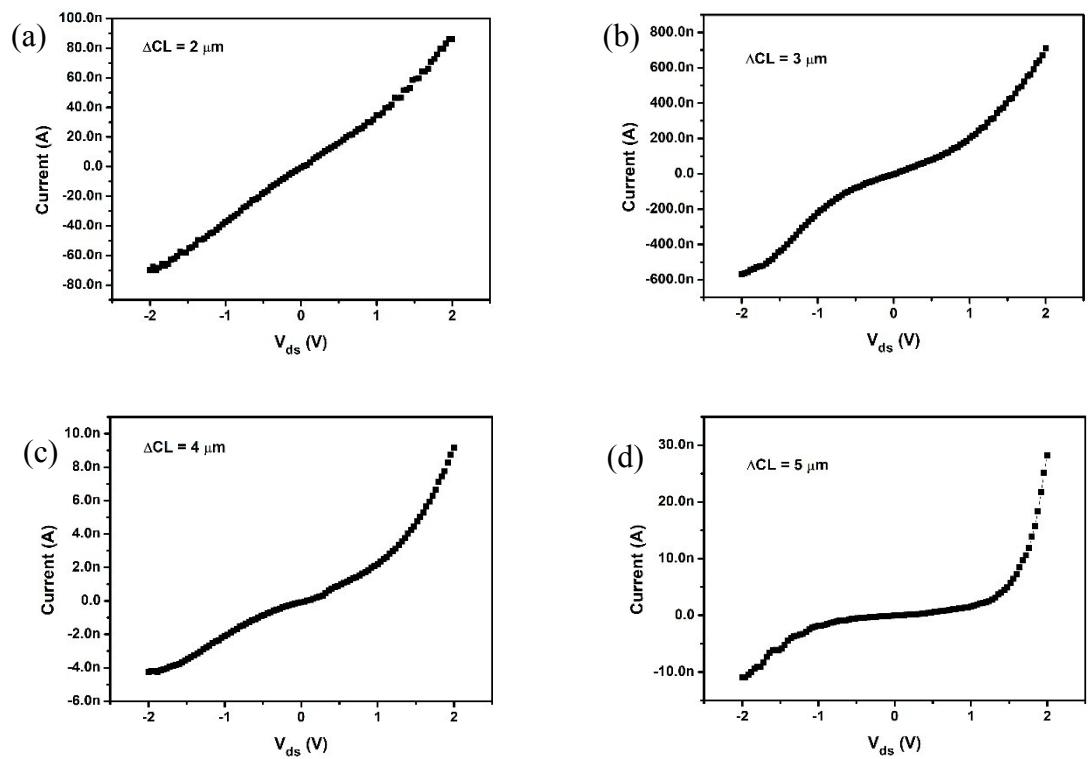


Figure S9. I-V curves of the AC-In₂S₃ photodetectors with various ΔCL : (a) 2 μm ; (b) 3 μm ; (c) 4 μm ; (d) 5 μm .

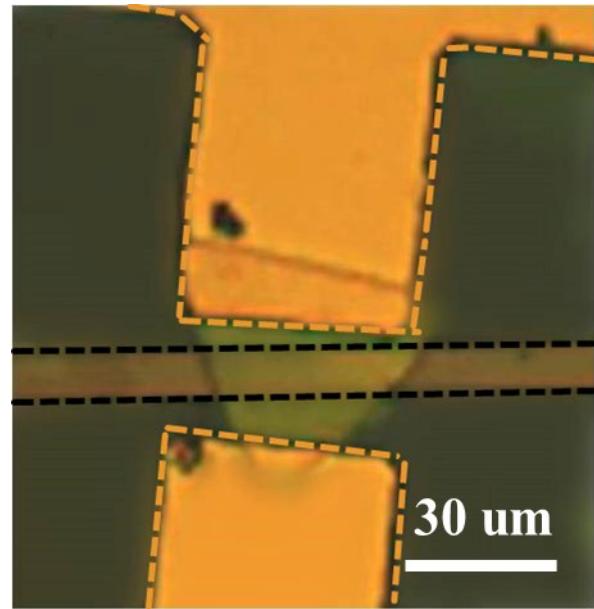


Figure S10. Optical image of the AC-In₂S₃/Si device with Au electrodes.

Table S1. Key parameters of our AC-In₂S₃/Si device and other asymmetric electrode material contact photodetectors.

Devices	Voc (mV)	Rectifi- cation ratio	R (mA/ W)	D* (Jones)	On/off ratio	Rise/decay time (ms)	Ref.
AC-In ₂ S ₃ /Si	300	ND	740	1.56×10^{10}	9×10^4	9/10	Ours
AC-In ₂ S ₃	5	2858	260	6.48×10^9	929	65/15	Ours
In ₂ S ₃	ND	148	ND	ND	329	461/20	Ours
Au/MoS ₂ /Mo ₂ C	ND	ND	0.1	ND	ND	23000/28000	⁵
Au/graphene/Ti	ND	ND	52	ND	ND	ND	⁶
Au/InSe/In	ND	ND	369	3.35×10^{12}	ND	ND	⁷
Pt/GaN/Ni	ND	ND	30	1.78×10^{12}	ND	100/100	⁸
Ag/ZnO/Au	ND	ND	ND	ND	ND	100/100	⁹
UCNPs/Gr/GaAs	430	ND	5.97	1.1×10^{11}	3.9×10^3	ND	¹⁰
Ag/ZnMgO/ZnO	ND	ND	16	5×10^9	ND	2400/3000	¹¹

Ref.: reference. ND: no data. Gr: graphene.

Table S2. Key parameters of our asymmetric AC-In₂S₃/Si device and other asymmetric heterojunction contact photodetectors.

Devices	Voc (mV)	Rectifi- cation ratio	R (mA/W)	D* (Jones)	On/off ratio	Rise/decay time (ms)	Ref.
AC-In ₂ S ₃ /Si	300	ND	740	1.56×10^{10}	9×10^4	9/10	Ours
AC-In ₂ S ₃	5	2858	260	6.48×10^9	929	65/15	Ours
In ₂ S ₃	ND	148	ND	ND	329	461/20	Ours
Sb-doped ZnO	ND	ND	0.15	9.9×10^8	ND	22000/100	¹²
MoS ₂ /WS ₂	ND	ND	4.36	4.36×10^{13}	ND	~4	¹³
CuO/Si	ND	ND	389	3×10^9	ND	0.06/0.08	¹⁴
ZnO/CuSCN	37	ND	20	ND	ND	ND	¹⁵
NiO/TiO ₂	ND	ND	0.065	1.1×10^9	14	1200/7100	¹⁶
MoS ₂ /h-BN/Gr	ND	ND	360	5.9×10^{14}	ND	ND	¹⁷

Ref.: reference. ND: no data. Gr: graphene.

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